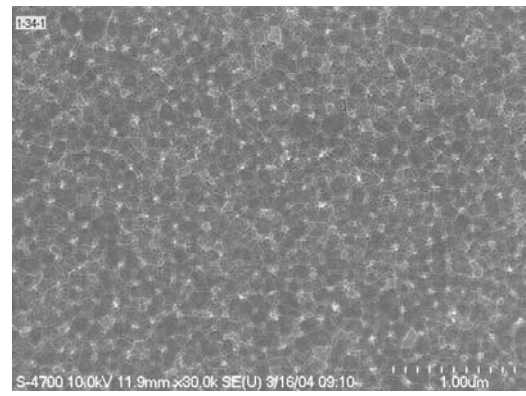
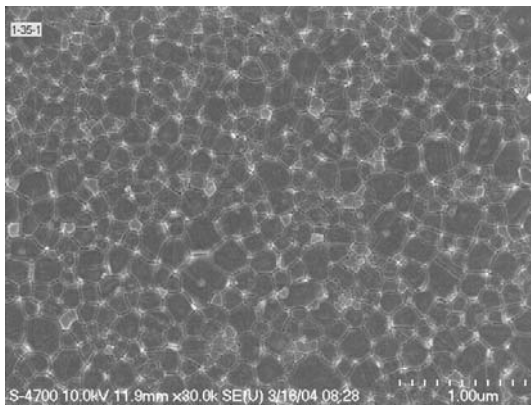


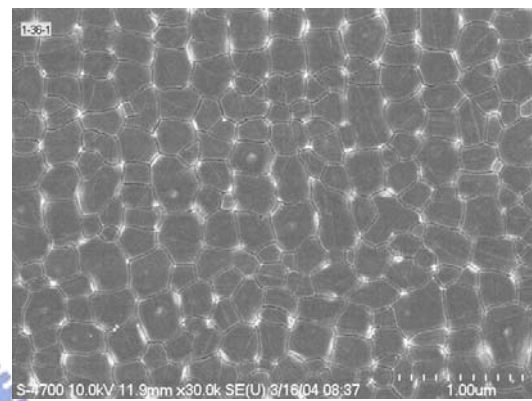
(a)



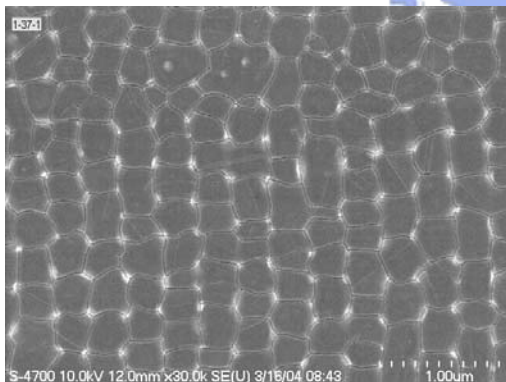
(b)



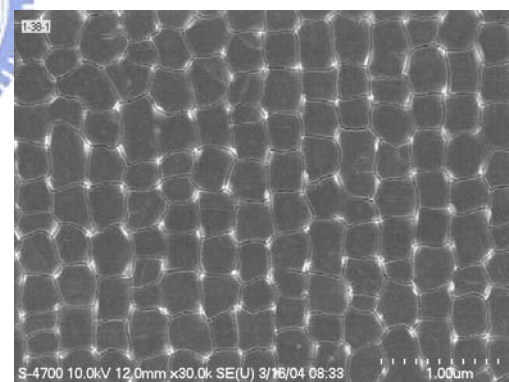
(c)



(d)

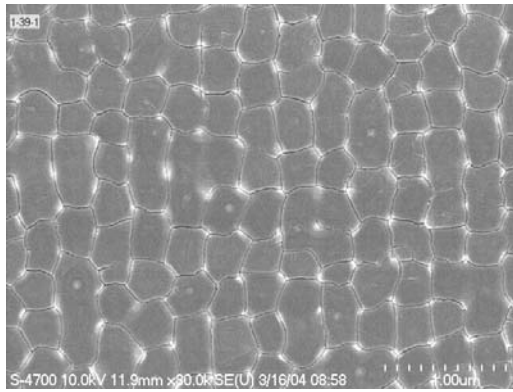


(e)

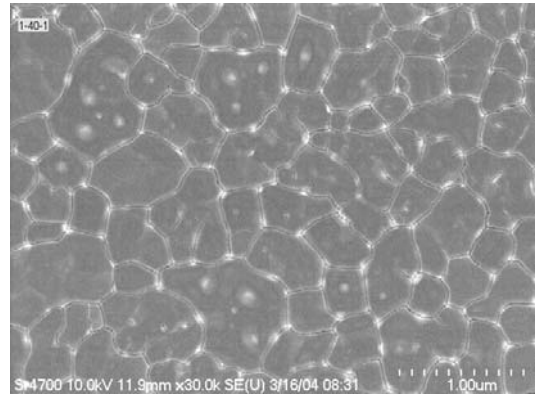


(f)

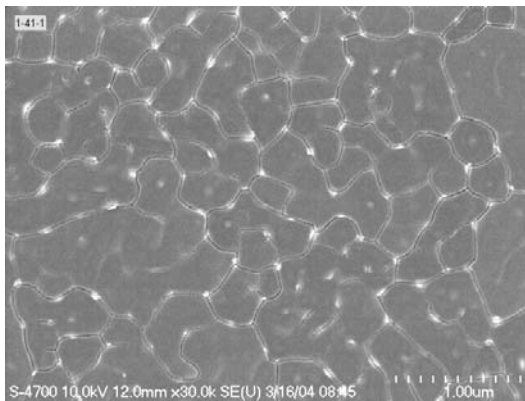
**Fig. 3-4** SEM micrographs of excimer laser crystallized poly-Silicon films after Secco etching for 60sec treatment. The applied laser energy densities are (a) 330, (b) 340, (c) 350, (d) 360 (e) 370 (f) 380  $\text{mJ}/\text{cm}^2$ . The laser energy 950mJ, frequency 100Hz, power 285W, scan speed 2mm/sec, pitch 0.02mm, beam width 0.4mm, pre treatment clean with HF+O3



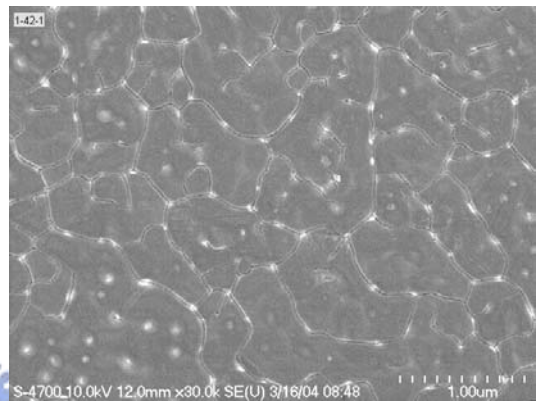
(a)



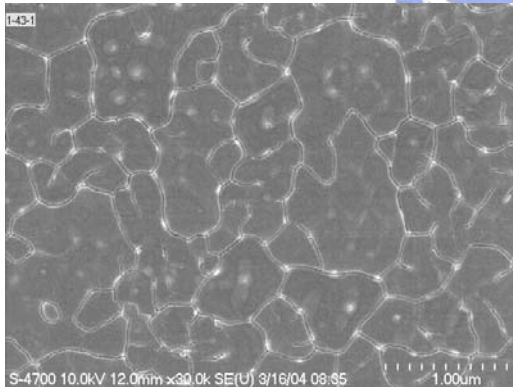
(b)



(c)



(d)



(e)

**Fig. 3-5** SEM micrographs of excimer laser crystallized poly-Silicon films after Secco etching for 60sec treatment. The applied laser energy densities are (a) 390, (b) 400, (c) 410, (d) 420 (e) 430  $\text{mJ}/\text{cm}^2$ . The laser energy 950mJ, frequency 100Hz, power 285W, scan speed 2mm/sec, pitch 0.02mm, beam width 0.4mm, pre treatment clean with HF+O3